	Hits	Search Text	DBs
3	2	((resist or photoresist or photosensitive) same develop$4 smae (wafer or holder or substrate) same (rotat$4 or spin$5) same (surfactant or hydrphilic$5 or hydrophob$5 or (surface near9 (modification or modify$4 or active) near9 agent))) and (surfactant same (resist or photoresist) same (expos$4 or illuminat$4 or irradiat$4) same (hold$3 or stage or chuck) same (rotat$5 or spin$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	5	((resist or photoresist or photosensitive) same develop$4 smae (wafer or holder or substrate) same (rotat$4 or spin$5) same (surfactant or hydrophilic$5 or hydrophob$5 or (surface near9 (modification or modify$4 or active) near9 agent))) and ((surfactant or (defect near5 preven$5 near9 agent) or (surface near9 (modifying or modification))) same (resist or photoresist) same (expos$4 or illuminat$4 or irradiat$4) same (hold$3 or stage or chuck) same (rotat$5 or spin$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
5	11	((resist or photoresist or photosensitive) same develop$4 smae (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4) same (rotat$4 or spin$5) same (surfactant or hydrophilic$5 or hydrophob$5 or (surface near9 (modification or modify$4 or active) near9 agent))) and ((surfactant or (defect near5 preven$5 near9 agent) or (surface near9 (modifying or modification))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same (rotat$5 or spin$5) same (dry$3 or heat$3 or bak$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	4	((resist or photoresist or photosensitive) same develop$4 same (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4) same (rotat$4 or spin$5) same (dry$5 or remov$4 or rins$4 or displac$4 or replac$4 or uniform$5 or strip$5)) and ((surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near12 (modifying or modification or active))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same (rotat$5 or spin$5) same (dry$3 or heat$3 or bak$4)) and ((wet$5 or surfactant) same ((contact near16 angle) or hydrophob$5 or hydrophil$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	6	((resist or photoresist or photosensitive) same develop$4 same (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4) same (rotat$4 or spin$5) same (dry$5 or remov$4 or rins$4 or displac$4 or replac$4 or uniform$5 or strip$5)) and ((surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near12 (modifying or modification or active))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same (rotat$5 or spin$5) same (dry$3 or heat$3 or bak$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	16	((resist or photoresist or photosensitive) same develop$4 same (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4) same (rotat$4 or spin$5) same (dry$5 or remov$4 or rins$4 or displac$4 or replac$4 or uniform$5 or strip$5)) and ((surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near16 (modifying or modification or active or treat$5))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same (rotat$5 or spin$5) same (dry$3 or heat$3 or bak$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	10	((resist or photoresist or photosensitive) same develop$4 same (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4)) and ((resist or photoresist) same (rotat$4 or spin$5) same (dry$5 or remov$4 or rins$4 or displac$4 or replac$4 or uniform$5 or strip$5) same develop$6) and ((surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near16 (modifying or modification or active))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same (rotat$5 or spin$5) same (dry$3 or heat$3 or bak$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	1	134/24.ccls. and develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	9	"134"/$.ccls. and develop$5 and (nozzle same (shape or geometr$6) same (band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	5	"396"/$.ccls. and develop$5 and (nozzle same (shape or geometr$6) same (band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	153	develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	1	(develop$5 same nozzle same (shape or geometr$6) same (band or rectang$4) same (plural$5 or multilple)) and (nozzle same (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	2	(develop$5 same nozzle same (shape or geometr$6) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4) same (plural$5 or multilple)) and (nozzle same (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	7	(develop$5 same nozzle same (shape or geometr$6) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4) same (plural$5 or multilple)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	1	430/311.ccls. and develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	5	"430"/$.ccls. and develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	20	((resist or photoresist or photosensitive) same develop$4 same (wafer or holder or substrate) same (expos$4 or illuminat$4 or irradiat$4)) and ((surface$4active or surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near16 (modifying or modification or active))) same (resist or photoresist) same (hold$3 or stage or chuck or mount$4) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	40	((resist or photoresist or photosensitive) same develop$4 same (expos$4 or illuminat$4 or irradiat$4)) and ((surface$4active or surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary$4 or var$5 or adjust$$ or chang$4 or alter$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	157	((resist or photoresist or photosensitive) same develop$4 same (expos$4 or illuminat$4 or irradiat$4)) and ((surface$4active or surfactant or (defect$5 near12 preven$5 near12 agent) or (surface near16 (modifying or modification or active))) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	1	396/627.ccls. and develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4)) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	3	396/627.ccls. and develop$5 and (nozzle same (multiple or pluralit$4) same (shape or geometr$6) same (cylindrical or circular or circle or band or rectang$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	5	(develop$5 same nozzle same (shape or geometr$6) same (band or rectang$4) same (plural$5 or multilple)) and ((resist or photoresist) same (expos$4 or illumiant$4 or irradiat$4) same develop$4) and (surface$4active or (surface near9 (active or modifying or modification or alter$4)) or surfactant or (defect near6 prevent$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	8	(develop$5 same nozzle same (shape or geometr$6) same (band or rectang$4) same (plural$5 or multilple)) and ((resist or photoresist) same (expos$4 or illumiant$4 or irradiat$4) same develop$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB